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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/603,852	06/25/2003	Kenneth C. Wu	ASC-022CPCN	3708
51414	7590 03/02/2006		EXAMINER	
GOODWIN PROCTER LLP			OWENS, DOUGLAS W	
	PATENT ADMINISTRATOR EXCHANGE PLACE			PAPER NUMBER
BOSTON, N	MA 02109-2881		2811	
			DATE MAILED: 03/02/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

			PV			
	Application No.	Applicant(s)				
	10/603,852	WU ET AL.				
Office Action Summary	Examiner	Art Unit				
	Douglas W. Owens	2811				
The MAILING DATE of this communication ap Period for Reply	ppears on the cover sheet with	the correspondence ac	ddress			
A SHORTENED STATUTORY PERIOD FOR REP THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a re - If NO period for reply is specified above, the maximum statutory perior - Failure to reply within the set or extended period for reply will, by statu Any reply received by the Office later than three months after the maili earned patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, may a reply ply within the statutory minimum of thirty (3 d will apply and will expire SIX (6) MONTH tte, cause the application to become ABAN	be timely filed 0) days will be considered time 5 from the mailing date of this of DONED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 12	December 2005.					
2a)⊠ This action is FINAL . 2b)☐ Th	is action is non-final.					
3) Since this application is in condition for allow) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
closed in accordance with the practice under	Ex parte Quayle, 1935 C.D. 1	1, 453 O.G. 213.				
Disposition of Claims						
4)⊠ Claim(s) See Continuation Sheet is/are pend	ing in the application.					
4a) Of the above claim(s) is/are withdra	awn from consideration.					
5) Claim(s) See Continuation Sheet is/are allow	red.					
6)⊠ Claim(s) <u>126-128,179 and 180</u> is/are rejected	d.					
7)⊠ Claim(s) <u>242-244</u> is/are objected to.						
8) Claim(s) are subject to restriction and	or election requirement.					
Application Papers						
9) The specification is objected to by the Examir	ner.					
10) The drawing(s) filed on is/are: a) ac	ccepted or b) objected to by	the Examiner.				
Applicant may not request that any objection to th	e drawing(s) be held in abeyance	. See 37 CFR 1.85(a).				
Replacement drawing sheet(s) including the corre	ection is required if the drawing(s)	is objected to. See 37 C	FR 1.121(d).			
11) The oath or declaration is objected to by the E	Examiner. Note the attached C	Office Action or form P	TO-152.			
Priority under 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreig a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 	nts have been received.					
3. Copies of the certified copies of the pri			Stage			
application from the International Bure	•		ŭ			
* See the attached detailed Office action for a lis		ceived.				
Attachment(s)						
1) D Notice of References Cited (PTO-892)	4) T Interview Sum	nmary (PTO-413)				
2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/N	fail Date				
 Information Disclosure Statement(s) (PTO-1449 or PTO/SB/0- Paper No(s)/Mail Date 12/12/05. 	8) 5) ☐ Notice of Info 6) ☐ Other:	rmal Patent Application (PT	O-152)			

Continuation of Disposition of Claims: Claims pending in the application are 126-129,133,134,140-143,159-170,177-182,188-197,200,204,208-235,239 and 242-244.

Continuation of Disposition of Claims: Claims allowed are 129,133,134,140-143,159-170,177,178,181,182,188-197,200,204,208-232,234,235 and 239.

Application/Control Number: 10/603,852 Page 2

Art Unit: 2811

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

2. Claims 126 – 128, 179 and 178 are rejected under 35 U.S.C. 102(e) as being anticipated by US Patent No. 5,963,817 to Chu et al.

Regarding claims 126 – 128 Chu et al. teach a semiconductor structure (Figs. 2 and 3, for example) comprising:

a layer structure comprising an etch-stop layer (29) and having a doping level below 10¹⁸ atoms/cm³ (it is not doped) and a substantially relaxed layer (16) comprising Si_{1-x}Ge_x; and

wherein the relaxed layer is graded and x<0.2 (Col. 2, lines 22-40).

Regarding claims 179 and 180, Chu et al. teach a method form forming a semiconductor substrate, the method comprising:

providing a first substrate (14); and

forming a layer structure over the first substrate by:

forming a substantially relaxed graded layer comprising $Si_{1-x}Ge_x$ (16) over the substrate; and

Application/Control Number: 10/603,852

Art Unit: 2811

forming a uniform etch-stop layer (29) over the graded layer, the uniform etch-stop layer having a doping level below 10¹⁸ atoms/cm³.

Allowable Subject Matter

- 3. Claims 129, 133, 134, 140 143, 159 170, 177 182, 188 197, 200, 204, 208 235 and 239 are allowed.
- 4. Claims 242 244 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Response to Arguments

5. Applicant's arguments filed December 12, 2005 have been fully considered but they are not persuasive.

Applicant argues that Chu et al. do not teach an etch-stop layer comprising a semiconductor material. This feature can be seen in Figs. 1 and 2, where the Si₃N₄ etch-stop layer comprises Silicon, which is a semiconductor material.

Conclusion

6. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any

Art Unit: 2811

extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Douglas W. Owens whose telephone number is 571-272-1662. The examiner can normally be reached on Monday-Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Eddie C. Lee can be reached on 571-272-1732. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Douglas W Owens

Examiner
Art Unit 2811

Dougla K. Owen